

# EAST Search History

*FWS*

Ref #	Hits	Search Query	DBs	Default Operat or	Plural s	Time Stamp
L5	236	((wafer or substrate or semiconductor) near5 (wash\$4 or clean\$4 or decontaminat\$4 or etch\$4 or remov\$4)) AND ((FOAM OR BUBBLE OR SUDS OR FROTH OR LATHER) NEAR2 (NOZZLE OR APPLICATOR OR SPRAY\$4 OR SPOUT OR DISTRIBUTOR)) AND ((NOZZLE OR APPLICATOR OR SPRAY\$4 OR SPOUT OR DISTRIBUTOR) NEAR2 (MOVABLE OR MOVES OR MOVING OR TRANSLATE OR AMBULATORY OR ADVANC\$4 OR SCAN\$4 OR DISPLAC\$4))	US-PGPU B; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB	OR	ON	2007/12/10 08:32
L6	192	((wafer or substrate or semiconductor) near2 (wash\$4 or clean\$4 or decontaminat\$4 or etch\$4 or remov\$4)) AND ((FOAM OR BUBBLE OR SUDS OR FROTH OR LATHER) NEAR2 (NOZZLE OR APPLICATOR OR SPRAY\$4 OR SPOUT OR DISTRIBUTOR)) AND ((NOZZLE OR APPLICATOR OR SPRAY\$4 OR SPOUT OR DISTRIBUTOR) NEAR2 (MOVABLE OR MOVES OR MOVING OR TRANSLATE OR AMBULATORY OR ADVANC\$4 OR SCAN\$4 OR DISPLAC\$4))	US-PGPU B; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB	OR	ON	2007/12/10 08:37